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#### U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
—	AA					
—	AB					

#### FOREIGN PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Country	Translation (Yes or No)
—	AC			
—	AD			

#### OTHER DOCUMENTS

SK	AE	E.P. Gusev et al., "Ultrathin high-K gate stacks for advanced CMOS devices," International Electron Devices Meeting Technical Digest (2001), pp. 451-454.
SK	AF	W. Zhu et al., "HfO <sub>2</sub> and HfAlO for CMOS: Thermal Stability and Current Transport," International Electron Devices Meeting Technical Digest (2001), pp. 463-466.
SK	AG	Y. Tamura et al., "Electrical characteristics of SiO <sub>2</sub> /High-k stacked gate insulator," Extended Abstracts (The 49 <sup>th</sup> Spring Meeting, 2002); The Japan Society of Applied Physics and Related Societies, No. 2, 28p-A-10, p.820.

Examiner

Date Considered

8/18/05